

ALICE ITS 3

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ALICE and ITS(s)



General purpose detector at LHC:

- Tracking (100 MeV/c 100 GeV/c)
- Particle identification: π , K, p, e (0.1 50 GeV/c)

ITS 1 (LHC Run 1/2)

- Hybrid pixels
- Pixels: 50×425 μm²
- C4F10 cooling
- ~ 1.1 % X₀

ITS 2 (LHC Run 3)

- MAPS
- Pixels: 27×29 μm²
- Water cooling
- ~ 0.3 % X₀ (inner layers)

ITS 3 (LHC Run 4)

- Stitched MAPS
- Pixels: ~20×22.5 μm²
- Air cooling
- $\sim 0.05 \% X_0$ (inner layers)



Excellent performance for small bent sensors

In 2020 50 µm thick ALPIDE chip bent to 22 mm along columns showed excellent efficiency in the beam test





https://doi.org/10.1016/j.nima.2021.166280

Excellent performance for small bent sensors

In 2021 μ *ITS3* – assembly of 3 ALPIDE sensors bent to ITS3 radii (18, 24, 30 mm) along rows – tested and also showed excellent detection efficiency not depending on the radius





ITS3 requires large sensors \rightarrow New CMOS process is needed

- ITS3 sensors size up to ~27×9 cm²
- Can only be produced via stitching on 12-inch wafers
- Available from Tower Partners Semiconductor Co. TPSCo in 65 nm
 - Continuation of TJ 180 nm used in ITS2
 - Custom process modifications for full depletion ported from TJ180
 - Lower power consumption
 - Potentially better radiation hardness



Wafer Ø = 300 mm (12")

Layer 2 sensor: 266 x 98 mm²

MLR1: first TPSCo 65 nm submission for technology validation

- Submitted Dec 2020 -> Delivered July 2021
- Three main goals:
 - Learn technological features
 - Characterize charge collection
 - Validate radiation hardness
- Large variety of small chips (1.5×1.5 mm²)
 - Analogue and digital blocks
 - 3 pixel matrices: APTS, CE65 and DPTS
- Standard process + 2 modified for better depletion:
 - "Modified" low dose n-type blanket
 - "Modified with gap" same as above with gaps on pixel edge



Modified







Pixel chips: APTS, CE65, DPTS



APTS (Analogue Pixel Test Structure)

- 6×6 pixel matrix
- Direct analogue readout of central 4×4 submatrix
- Two types of output drivers:
 - Source follower (APTS-SF)
 - Very fast OpAmp (APTS-OA)
- AC/DC coupling
- 4 pitches: 10, 15, 20, 25 μm
- 3 process variations



CE65 (Circuit Exploratoire 65 nm)

- 2 matrix sizes
 - 64×32 with 15 μ m pitch
 - 48×32 matrix with 25 μm pitch
- Rolling shutter readout (50 μs integration time)
- 3 in-pixel architectures:
 - AC-coupled amplifier
 - DC-coupled amplifier
 - Source follower
- 4 chip variants:
 - Standard process 15 μm pitch
 - Modified process 15 μm pitch
 - Modified process with gaps 15 µm pitch
 - Standard process 25 μm pitch



DPTS (Digital Pixel Test Structure)

- 32×32 pixel matrix
- Asynchronous digital readout
- Time-over-Threshold information
- Pitch: 15×15 μm²
- Only "modified with gap" process modification

Characterization results: effect of modified process

- Process modifications make almost all the charge to be collected by seed pixel due to full depletion of epi-layer
- This effect greatly extends working range with excellent detection efficiency



Detection efficiency and FHR vs. irradiation

- Detection efficiency decreases with NIEL dose
- FHR increases with TID dose
- Perfect performance at ITS3 combined level of 10 kGy + 10¹³ n_{eq} /cm²



Spatial resolution and cluster size vs. irradiation

- Spatial resolution isn't affected by irradiation
- Cluster size slightly increases with NIEL irradiation
- Resolution is compatible 3.25
 with mostly single pixel 3.00
 clusters and digital 2.75
 readout 2.50



Spatial resolution and cluster size vs. pitch

- Weak dependence of cluster size on pixel pitch
- Spatial resolution of about 5 μm for expected pitch value of 22 μm



DPTS: Temporal resolution ~7 ns



ER1: First submission of stitched chips

- Submitted Dec 2022
- Received May 2023
- Two types of stitched chips:
 - MOSS (259×14 mm²)
 - MOST (259×2.5 mm²)
- 1/10 versions of MOSS(T)
 - Baby-MOSS
 - Baby-MOST
- Multiple small chips (1.5×1.5 mm²)



MOSS - <u>MO</u>nolithic <u>S</u>titched <u>S</u>ensor



Challenging handling of stitched chips



MOSS on the carrier card



MOSS test system

Three different types of board:

• Carrier card

- 5x proximity cards
 - 1 card x 4 quadrants
 - 1 top/bottom halves
- 5x automation and readout modules to steer the proximity boards and interface the sensor control and readout with a computer



MOSS – first test results



- 16 MOSS bonded and being tested
- Collecting data on the yield
- First chips tested with the beam



Summary and outlook

- Bending of MAPS down to 18 mm doesn't affect their performance
- TPSCo 65 nm CMOS process is validated for ITS3:
 - Spatial resolution: ~ 5 μm
 - Radiation hardness: $10 \text{ kGy} + 10^{13} \text{ n}_{eq} / \text{cm}^2$
- First stitched prototypes work and being tested
- ER2 submission in preparation: final full scale sensor prototype
- TDR to be presented to LHCC in November 2023

